Notice of Allowability	Application No.	Applicant(s)	Applicant(s)	
	10/719,704	CASEY ET AL.	CASEY ET AL.	
	Examiner	Art Unit		
	Hsien-ming Lee	2823		
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
1. This communication is responsive to 9/10/04.				
2. The allowed claim(s) is/are <u>1-11</u> .				
3. The drawings filed on 15 December 2003 are accepted by the Examiner.				
 4. ☐ Acknowledgment is made of a claim for foreign priority una) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 	e been received. e been received in Applicati cuments have been receive of this communication to fil	ion No ed in this national stage applicati		
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			OTICE OF	
6. CORRECTED DRAWINGS (as "replacement sheets") mus (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the state of the sheet.	son's Patent Drawing Revie s Amendment / Comment o .84(c)) should be written on	or in the Office action of the drawings in the front (not the	back) of	
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.				
 Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date 112103 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material 	6. ☐ Interview 9 Paper No 08), 7. ☑ Examiner	nformal Patent Application (PTO Summary (PTO-413), ./Mail Date s Amendment/Comment s Statement of Reasons for Allow HSIEN-MING LEE PRIMARY EXAMINED.	wance	

DETAILED ACTION

Remarks

1. Applicant's election without traverse to claims 1-11 is acknowledged.

Examiner's Amendment

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Leslie S. Szivos (Reg. No. 39,394) on Nov. 30, 2004.

3. The application has been amended as follows:

In claim 10, at line 2, replace the very last word "metal" into -- liner --.

Cancel non-elected claims 12-20.

Allowable Subject Matter

- 4. Claims 1-11 are allowed.
- 5. The following is an examiner's statement of reasons for allowance:

The closest prior art of record, Hart et al. to US 2004/0029303, disclose using a controlled pore glass (CPG) material as a substrate (paragraph [0025]). However, none of the prior art teaches or suggests forming the controlled pore glass (CPG) as an interlayer dielectric on a dense etch stop layer, subjecting the CPG to thermal treatment to form a distinct interpenetrating microstructure, including a substantially pure silicon dioxide network and a

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boron-rich network, and selectively removing the boron-rich network by acid etching to provide a reticulated porous network of substantially pure, amorphous silicon dioxide.

Therefore, the instant invention is neither anticipated nor rendered obvious over the prior art of record.

- 6. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."
- 7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday (8:00 \sim 6:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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Hsien-ming Lee Primary Examiner Art Unit 2823

Nov. 30, 2004

HSIEN-MING LEE
PRIMARY EXAMINERS